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**CO<sub>2</sub> Reduction Hot Paper**

# Facet-Selective Deposition of Ultrathin Al<sub>2</sub>O<sub>3</sub> on Copper Nanocrystals for Highly Stable CO<sub>2</sub> Electroreduction to Ethylene

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**Abstract:** Catalysts based on Cu nanocrystals (NCs) for electrochemical CO<sub>2</sub>-to-C<sub>2+</sub> conversion with high activity have been a subject of considerable interest, but poor stability and low selectivity for a single C<sub>2+</sub> product remain obstacles for realizing sustainable carbon-neutral cycles. Here, we used the facet-selective atomic layer deposition (FS-ALD) technique to selectively cover the (111) surface of Cu NCs with ultrathin Al<sub>2</sub>O<sub>3</sub> to increase the exposed facet ratio of (100)/(111), resulting in a faradaic efficiency ratio of C<sub>2</sub>H<sub>4</sub>/CH<sub>4</sub> for overcoated Cu NCs 22 times higher than that for pure Cu NCs. Peak performance of the overcoated catalyst (Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C) reaches a C<sub>2</sub>H<sub>4</sub> faradaic efficiency of 60.4% at a current density of 300 mA cm<sup>-2</sup> in 5 M KOH electrolyte, when using a gas diffusion electrode flow cell. Moreover, the Al<sub>2</sub>O<sub>3</sub> overcoating effectively suppresses the dynamic mobility and the aggregation of Cu NCs, which explains the negligible activity loss and selectivity degradations of Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C shown in stability tests.

## Introduction

Developing highly efficient electrocatalysts for converting CO<sub>2</sub> into value-added chemical fuels provides a feasible pathway for renewable energy storage while reducing the depletion of fossil resources.<sup>[1]</sup> Colloidal copper-based nanocrystals (Cu NCs) with various sizes, shapes, exposed facets, oxidation states, and surface ligands have been widely studied as electrocatalysts that can form multiple hydrocarbon products. However, the efficiency and selectivity are still too low for industrial-scale implementation.<sup>[2,3]</sup> Hori and Takahashi et al. have demonstrated that the Cu (100) facet facilitates the formation of ethylene while the Cu (111) facet favors methane generation.<sup>[4,5]</sup> This model catalyst study has inspired

the exploration of colloidal Cu NCs with dominantly exposed (100) facets for enhancing CO<sub>2</sub>-to-C<sub>2</sub>H<sub>4</sub> selectivity.<sup>[6,7]</sup> However, these shape-controlled nanocrystals underwent unpredictable surface reconstructions and size changes during catalysis, which led to the loss of the initially well-defined facets and a decrease of favorable active sites.<sup>[8–10]</sup> Although particle confinement and surface ligand engineering strategies have been developed to mitigate the degradation of electrocatalytic activity on metal nanoparticles,<sup>[11,12]</sup> more effective surface modification tools are demanded to stabilize the Cu NCs for high yield CO<sub>2</sub>-to-C<sub>2</sub>H<sub>4</sub> conversion under high current density.

Atomic layer deposition (ALD), a gas phase ultrathin film deposition technique based on self-limiting reactions, has been widely utilized to fabricate inert oxide overcoating with precise thicknesses on metal nanoparticle catalysts to prevent their coalescence under harsh reaction conditions.<sup>[13,14]</sup> A thermal post-treatment process is generally adopted to convert the continuous overcoating into porous channels to promote reactant diffusion and accessibility of active surface sites, which will alter the surface morphologies and structures of underlying nanoparticles at high temperature.<sup>[15,16]</sup> Area-selective ALD (AS-ALD) has been shown to selectively deposit an ultrathin oxide layer onto the desired sites of nanoparticle catalysts. Still, the surface-functionalized organic molecules for area blocking must be removed to enhance the intimate contact at the interface.<sup>[17,18]</sup> By contrast, facet-selective ALD (FS-ALD) provides a more straightforward way to passivate or activate the desired sites via the intrinsic differences in binding energies of metal precursor on various facets of metal nanoparticle catalysts.<sup>[19,20]</sup> Lu et al. demonstrated that the trimethylaluminum

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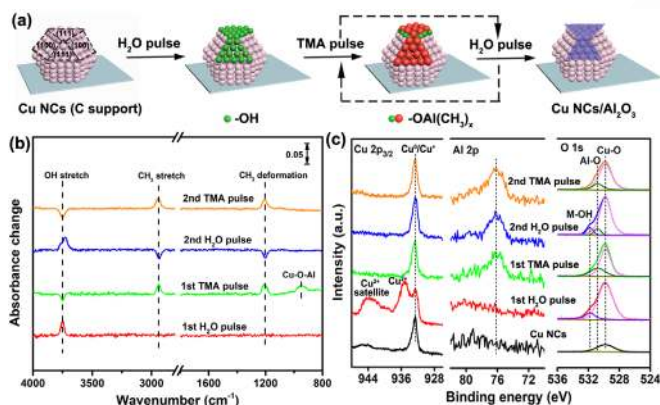
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(TMA) precursors have facet-selective adsorption behavior on Pt and Pd during thermal ALD of  $\text{Al}_2\text{O}_3$  layers, and the adsorption and dissociation of TMA on Cu (111) and Cu (100) are endothermic.<sup>[21]</sup> Therefore, a surface chemistry engineering approach is a promising means of preferentially depositing an inert  $\text{Al}_2\text{O}_3$  layer on Cu (111) facets while leaving Cu (100) facets intact, potentially enhancing  $\text{CO}_2$ -to- $\text{C}_2\text{H}_4$  selectivity and long-term stability.

In this work, we developed an “ $\text{H}_2\text{O}$ -TMA- $\text{H}_2\text{O}$ -TMA” pulse sequence to replace the typical “TMA- $\text{H}_2\text{O}$ -TMA- $\text{H}_2\text{O}$ ” cycles to deposit ultrathin  $\text{Al}_2\text{O}_3$  layer on supported Cu NCs (Figure 1a). The first  $\text{H}_2\text{O}$  pulse generates surface



**Figure 1.** a) Schematic diagram of  $\text{Al}_2\text{O}_3$  overcoated Cu nanocrystals generated with facet-selective ALD. b) In-situ infrared difference spectra and c) quasi in situ XPS of precursor dose cycles of the ALD process.

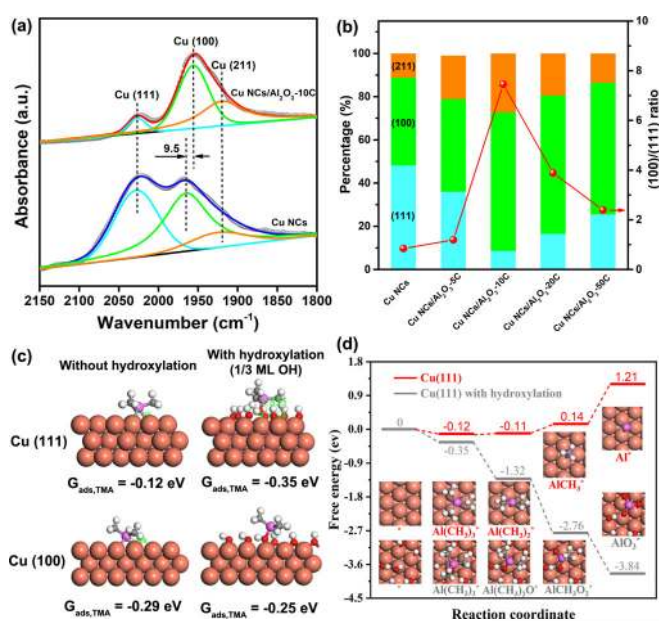
hydroxide groups on the Cu (111) facets, providing preferential nucleation sites for subsequent TMA adsorption and reaction. The Cu (100)/Cu (111) facet ratio for the optimized overcoated Cu NCs (10 cycles of ALD  $\text{Al}_2\text{O}_3$ , Cu NCs/ $\text{Al}_2\text{O}_3$ -10C) is 7.5 times that of Cu NCs, which leads to a 22 fold increase in the faradaic efficiency ratio of  $\text{C}_2\text{H}_4/\text{CH}_4$  in H-cell measurements. The overpotential for  $\text{CO}_2$ -to- $\text{C}_2\text{H}_4$  is also decreased, attributed to a lower reaction energy barrier for the critical step of hydrogenation of  $^*\text{CO}$ -CO to  $^*\text{CO}$ -COH. Cu NCs/ $\text{Al}_2\text{O}_3$ -10C achieves a stable 60.4% Faradaic efficiency for  $\text{C}_2\text{H}_4$  at a current density of  $300 \text{ mA cm}^{-2}$  in a polytetrafluoroethylene (PTFE)-based gas-diffusion electrode flow cell.

## Results and Discussion

The Cu NCs were synthesized by following a previously reported method, with slight modifications (see the Experimental Methods in Supporting Information).<sup>[22]</sup> The as-synthesized Cu NCs with pure cubic phase show a highly uniform spherical morphology with an average size of  $10.0 \pm 1.6 \text{ nm}$  (Figure S1). The Cu NCs were well dispersed on carbon black with clear lattice fringes of (111) facets (Figure S2a-d). After 10 cycles of ALD  $\text{Al}_2\text{O}_3$ , the Cu NCs were partially enclosed with an amorphous  $\text{Al}_2\text{O}_3$  layer with  $0.8 \pm 0.2 \text{ nm}$  thickness (Figure S2e-h). The overcoating thickness gradually increases with increasing ALD cycles of  $\text{Al}_2\text{O}_3$

(Figure S3). In-situ infrared spectroscopy was carried out to gain insight into the surface reactions on Cu NCs during the thermal ALD process. As shown in Figure 1b, infrared difference spectra of pulsed precursors were used to illustrate the formation and elimination of surface groups by observing signal gain and loss, respectively. Spectral signatures of surface hydroxyl groups were observed at around  $3752 \text{ cm}^{-1}$  after the first  $\text{H}_2\text{O}$  pulse. They then disappeared after the subsequent TMA pulse, while signatures of surface  $\text{CH}_3$  groups appeared/disappeared at around  $2945$  and  $1204 \text{ cm}^{-1}$  under TMA/ $\text{H}_2\text{O}$  pulses.<sup>[23]</sup> This alternating formation-consumption of surface groups is consistent with the self-limiting nature of typical ALD processes. A peak appeared at  $953 \text{ cm}^{-1}$  when delivering TMA precursors. It remained constant for the following cycles, indicating that the surface hydroxyl groups on Cu NCs were completely consumed by the first cycle of TMA, forming Cu-O-Al groups.<sup>[24]</sup> During the second cycle  $\text{H}_2\text{O}$  pulse, the hydroxyl peak splits into a minor peak at  $3770 \text{ cm}^{-1}$  and a major peak of  $3731 \text{ cm}^{-1}$ , suggesting the presence of two chemically distinct hydroxyl groups as the active sites for the ALD reaction process evolved from Cu-OH to Al-OH groups.<sup>[24]</sup> Quasi in situ X-ray photoelectron spectroscopy (XPS) was used to further investigate the surface chemistry of ALD doses,<sup>[25]</sup> and the high resolution spectra of Cu  $2p_{3/2}$ , Al  $2p$ , and O  $1s$  are shown in Figure 1c. Prior to ALD, the surface of the Cu NCs is composed of dominant metallic Cu and minor copper oxide species.<sup>[26]</sup> The first dose of  $\text{H}_2\text{O}$  generated a large amount of CuO species, as indicated by the appearance of a sharp peak at  $935.2 \text{ eV}$  and a satellite peak at  $943.9 \text{ eV}$ .<sup>[27]</sup> Moreover, surface hydroxyl groups with peaks at  $531.8 \text{ eV}$  are observed from O  $1s$  spectra during the first and second  $\text{H}_2\text{O}$  pulses, consistent with the above in situ IR results. Interestingly, all detectable CuO disappeared during the following TMA pulse due to the strong reduction capacity of TMA precursors. It should be noted that the peaks of metallic copper ( $\text{Cu}^0$ ) and copper (I) oxide are highly overlapped, and cannot rule out a certain amount of  $\text{Cu}_2\text{O}$  species on the surface. A peak at  $530.8 \text{ eV}$  from  $\text{Al}_2\text{O}_3$  is also observed, and a shift in the intensity of peaks at  $531.8 \text{ eV}$  to  $530.8 \text{ eV}$ , indicates the transition of Cu-OH to Al-O.

Diffuse reflectance infrared Fourier transform spectroscopy (DRIFTS) of CO chemisorption has been widely used to determine the exposed facet distribution on metal catalysts.<sup>[19-21]</sup> To confirm the facet-selective deposition mechanism of  $\text{Al}_2\text{O}_3$  on Cu NCs, this technique was carried out on Cu NCs and Cu NCs/ $\text{Al}_2\text{O}_3$ - $x\text{C}$  ( $x = 5, 10, 20, 50$ ) (Figure 2a and Figure S4). The three fitting peaks for the linear adsorption curves are assigned to CO adsorbed on the Cu (111) facet, Cu (100) facet, and low coordination Cu sites such as edges and corners (herein represented by Cu (211) facet), which matches well with the vibrational frequency peaks of calculated CO chemisorption (Figure S5 and Table S2). For the Cu NCs, the percentage of Cu (111) facet, Cu (100) facet, and Cu (211) over the surface is 48.2%, 40.6%, and 11.2%, respectively. After 5 ALD cycles of  $\text{Al}_2\text{O}_3$  deposited on Cu NCs, the percentage of Cu (111) decreases from 48.2% to 36.0%, indicating that the Cu (111) surface sites are preferentially covered. The percentage of Cu (111) further

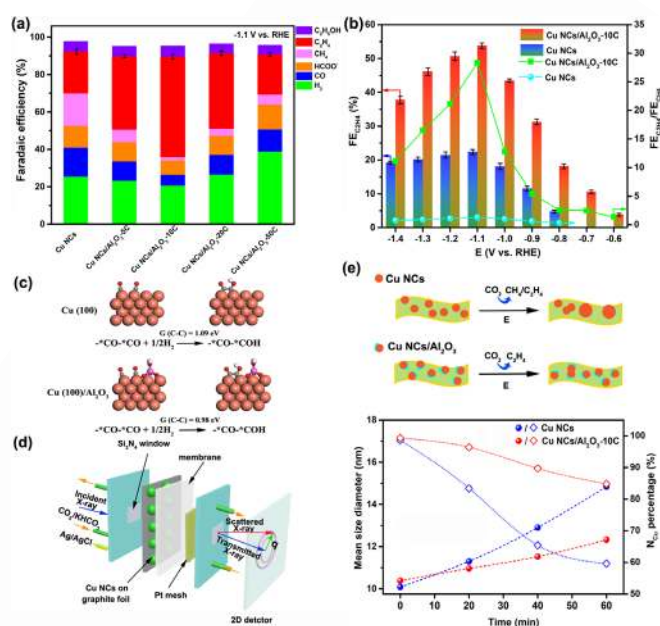


**Figure 2.** a) Fitted curves of DRIFTS CO linear adsorption peaks for Cu NCs and Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C catalysts. b) Facet percentage and (100)/(111) ratio of Cu NCs with different Al<sub>2</sub>O<sub>3</sub> cycles. c) Free energies of a TMA precursor adsorbed on Cu surfaces with/without hydroxylation. d) Free energy profile (at 200°C and 1 atm) for TMA dissociation on Cu (111) before and after hydroxylation.

decreases to 8.6% after 10 ALD cycles. However, excess ALD cycles start to cover Cu (100) facets, as indicated by a decrease in the integrated CO chemisorption peak area for Cu (100).

This facet-selective deposition process can be explained by the adsorption energy of TMA on different Cu facets, obtained from density functional theory (DFT) calculations. Figure 2c shows the calculated adsorption energies of TMA on Cu surfaces with or without hydroxylation. For the Cu surface without hydroxylation, the TMA molecule preferentially adsorbs on Cu (100) rather than Cu (111) indicated by the more negative adsorption energy. With hydroxylation, the trend reverses, with (111) binding TMA more strongly (−0.35 eV) than (100) does (−0.29 eV). Thus, the DFT calculations predict the preferential adsorption of TMA on Cu (111) after the H<sub>2</sub>O pulse that provides abundant surface \*OH. The DFT calculations also predict that surface \*OH promotes the dissociation of TMA. The free energy profile in Figure 2d indicates that the TMA dissociation to Al\* via Al(CH<sub>3</sub>)<sub>2</sub>\* and AlCH<sub>3</sub>\* is exothermic with \*OH at 200°C. Such a process is not possible in pure Cu(111) (Figure 2d) or Cu (100) (Figure S6). Thus, the DFT calculations predict that TMA can decompose into Al<sub>2</sub>O<sub>3</sub> that coated on Cu (111) surface, which well explains the experimental observations.

The CO<sub>2</sub> reduction reaction (CO<sub>2</sub>RR) performance of Cu NCs with various ALD cycles was firstly evaluated in a three-electrode H-cell containing CO<sub>2</sub>-saturated 0.5 M KHCO<sub>3</sub> as the flowing electrolyte. The geometric current density gradually decreased with increasing ALD cycles, as surface sites were blocked by the inert Al<sub>2</sub>O<sub>3</sub> overcoating (Figure S7). Figure 3a shows the Faradaic efficiency (FE) of gas and liquid products over Cu NCs with various ALD cycles at a constant



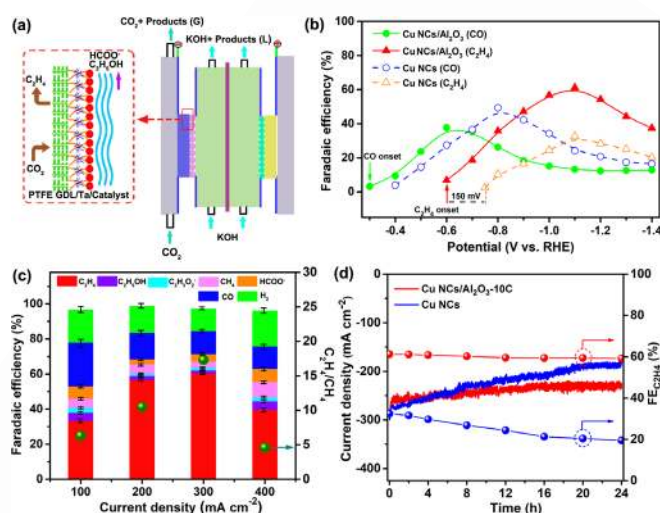
**Figure 3.** a) Faradaic efficiency (FE) of CO<sub>2</sub>RR products for Cu NCs with different ALD cycles of Al<sub>2</sub>O<sub>3</sub> overcoating at a constant potential of −1.1 V vs. RHE. The error bars indicate the standard deviation of three independent measurements. b) FE<sub>C<sub>2</sub>H<sub>4</sub></sub> and FE<sub>C<sub>2</sub>H<sub>4</sub></sub>/FE<sub>CH<sub>4</sub></sub> ratio versus the potential for Cu NCs and Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C. c) The calculated free energy differences of hydrogenation of dimerized \*CO\*CO on Cu (100) and Cu (100)/Al<sub>2</sub>O<sub>3</sub> from DFT calculation. d) Schematic diagram of an electrochemical flow cell for in situ small angle X-ray scattering (SAXS) characterization. e) Time-dependent mean size diameter and number density of nanocrystals from in situ SAXS, relative to the initial values at −1.1 V vs. RHE.

potential of −1.1 V vs. RHE. The FE of ethylene (FE<sub>C<sub>2</sub>H<sub>4</sub></sub>) for pure Cu NCs is only 22.4% due to the competing CH<sub>4</sub> formation and the sluggish C–C coupling steps.<sup>[28]</sup> After 5 ALD cycles of Al<sub>2</sub>O<sub>3</sub>, a 1.75 times increase in FE<sub>C<sub>2</sub>H<sub>4</sub></sub> and a 2.6 times decrease in FE<sub>CH<sub>4</sub></sub> were observed. As the Al<sub>2</sub>O<sub>3</sub> overcoating increases to 10 cycles, the FE<sub>C<sub>2</sub>H<sub>4</sub></sub> increases to an impressive value of 53.8%, while FE<sub>CH<sub>4</sub></sub> is reduced to 1.9%. By contrast, Cu NCs overcoated with 10 cycles Al<sub>2</sub>O<sub>3</sub> by using reverse precursor pulse sequences (TMA-H<sub>2</sub>O-TMA-H<sub>2</sub>O, denoted as Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C-R) shows a much lower FE<sub>C<sub>2</sub>H<sub>4</sub></sub> of 15.9%, consistent with preferential deposition of Al<sub>2</sub>O<sub>3</sub> on Cu (100) facets rather than Cu (111) facets (Figure S8). When the H<sub>2</sub>O-TMA-H<sub>2</sub>O-TMA ALD pulse cycles further increased to 20 and 50, the corresponding FE<sub>C<sub>2</sub>H<sub>4</sub></sub> decreases to 40.3% and 21.2%, respectively, and hydrogen becomes the dominant reaction product. Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C exhibits a 2.4-fold increase in FE<sub>C<sub>2</sub>H<sub>4</sub></sub> compared to the pure Cu NCs, consistent with the significant increase of (100)/(111) ratio on the NC surface. The trend of FE<sub>C<sub>2</sub>H<sub>4</sub></sub>/FE<sub>CH<sub>4</sub></sub> at various ALD cycles is consistent with their partial current density ratio at −1.1 V vs. RHE (Figure S9). The onset potential for C<sub>2</sub>H<sub>4</sub> generation over Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C is −0.6 V vs. RHE, which is more positive than that over Cu NCs. Such C<sub>2</sub> promotion is confirmed by DFT calculations showing a decrease of reaction energy of the potential-determining step (\*CO\*COH formation) from 1.09 eV to 0.98 eV (Figure 3c) on the Cu (100) surface. This large drop

implies that the heterointerface of Cu/Al<sub>2</sub>O<sub>3</sub> does indeed help with steering selectivity towards C<sub>2+</sub> products. Considering the inert nature of the Al<sub>2</sub>O<sub>3</sub> overcoating and negligible effects on the electronic structure of Cu NCs (Figure S7b and Figure S10), the heterogeneous interface of Cu/Al<sub>2</sub>O<sub>3</sub> mainly affects the adsorption orientation of neighbor \*CO intermediates and therefore decreases the reaction energy of the potential-determining C–C coupling step. As the potential became more negative, both the FE<sub>C<sub>2</sub>H<sub>4</sub></sub> and FE<sub>C<sub>2</sub>H<sub>4</sub></sub>/FE<sub>CH<sub>4</sub></sub> ratio reaches the maximum values of 53.8% and 28.3 at –1.1 V vs. RHE, respectively (Figure 3b). The electrochemically active surface area (ECSA) is estimated by measuring the electrical double-layer capacitance (Figure S11). The ECSA for Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C and Cu NCs is 17.5 and 36 cm<sup>2</sup>, respectively, and the ratio of ECSA-normalized partial current density for C<sub>2</sub>H<sub>4</sub> across the potential window is higher than 4.5 (Figure S12). Moreover, an enhancement of reaction kinetics for selective CO<sub>2</sub>-to-C<sub>2</sub>H<sub>4</sub> conversion and a faster interfacial charge transfer rate is observed after ALD Al<sub>2</sub>O<sub>3</sub> overcoating (Figure S13).

It is a great challenge to maintain the size and morphology of Cu-based nanoparticle catalysts during CO<sub>2</sub>RR and achieve long-term stability for producing specific C<sub>2+</sub> products. Both the total current density (*j*<sub>total</sub>) and FE<sub>C<sub>2</sub>H<sub>4</sub></sub> gradually decrease for Cu NCs held at –1.1 V vs. RHE, while negligible performance degradation is observed for Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C (Figure S14). The initially monodisperse Cu NCs aggregated into larger clusters with a wider size distribution range after 12 h electrolysis at –1.1 V vs. RHE (Figure S15a and b). The severe aggregation of Cu NCs leads to a 45.8% decrease of ECSA and 79.5% decrease in the ratio of (100)/(111) on nanocrystal surfaces (Figure S16). However, there is only a slight decrease, from 7.45 to 6.84, in (100)/(111) over the Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C after electrolysis. By contrast, these critical properties for Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C are well maintained since the Al<sub>2</sub>O<sub>3</sub> overcoating physically separates the nanocrystals and reduces the chance of migration and collision during CO<sub>2</sub>RR (Figure S15c and d). A slight surface reduction is observed on Cu NC/Al<sub>2</sub>O<sub>3</sub>-10C after electrolysis, suggesting that the metallic Cu<sup>0</sup> species act as the active sites for selective CO<sub>2</sub>RR (Figure S17).<sup>[29]</sup> In situ small angle X-ray scattering (SAXS) measurements using a custom-made electrochemical flow cell were carried out to track the size evolution of Cu NCs-based catalysts during CO<sub>2</sub>RR (Figure 3d and Figure S18). After 1 h electrolysis at –1.1 V vs. RHE, the mean size diameter for Cu NCs increases from 10.1 nm to 14.8 nm and relative number density decreases to 59.6% after 1 h electrolysis at –1.1 V vs. RHE (Figure 3e), suggesting that NC aggregation is likely the dominant mechanism for CO<sub>2</sub>RR activity degradation. By contrast, the ultrathin Al<sub>2</sub>O<sub>3</sub> overcoating mitigates the severe NC aggregation resulting in smaller changes of mean size diameter and relative number density.

In order to remove CO<sub>2</sub> mass transfer limitations and achieve higher partial current density towards ethylene production, we utilized a gas-feed flow electrolyzer to test the CO<sub>2</sub>RR activity of Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C in 5 M KOH electrolyte (Figure 4a and Figure S19). A PTFE-based gas diffusion electrode (GDE) with high surface hydrophobicity



**Figure 4.** a) Schematic diagram of the gas-feed flow electrolyzer with PTFE-based GDE configuration. b) A comparison of the potential-dependent FE<sub>CO</sub> and FE<sub>C<sub>2</sub>H<sub>4</sub></sub> for Cu NCs and Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C in 5 M KOH electrolyte. c) FE of product distribution for Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C as a function of current density. The resistance of the three-electrode system under OCV was evaluated and then 90% value for IR compensation was applied. d) Stability test of Cu NCs and Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C conducted at –1.1 V vs. RHE for 24 h.

was used as the substrate to avoid the typical “flooding” issue that is common for carbon-based GDEs.<sup>[30]</sup> Inert tantalum was sputtered onto the PTFE to endow the electrode with high conductivity without affecting the CO<sub>2</sub>RR of tested catalysts (Figure S20). The increase of KOH concentration provides higher electrolyte conductivity and lower ohmic losses which facilitates a larger current density (Figure S21). pH increase also suppresses the competing hydrogen evolution reaction (HER), together with the positive effect of the triple-boundary interface in promoting C–C coupling, as supported by the DFT calculations and other reported research.<sup>[31]</sup> A 150 mV shift in onset potential from Cu NCs to Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C is observed experimentally (Figure 4b). These observations can be explained by the DFT calculations showing a 0.11 eV decrease of the reaction energy barrier of the C–C coupling step after ALD overcoating. CO is the dominant product below –0.6 V vs. RHE, with FE<sub>CO</sub> being as high as 40% at –0.6 V vs. RHE. As the potential becomes more negative, FE<sub>CO</sub> decreases while FE<sub>C<sub>2</sub>H<sub>4</sub></sub> increases, suggesting that \*CO intermediates play a critical role in the C–C coupling step to form C<sub>2</sub>H<sub>4</sub>.<sup>[28]</sup> Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C shows a considerably higher peak FE<sub>C<sub>2</sub>H<sub>4</sub></sub> of 61.2% at –1.1 V vs. RHE, when compared with the Cu NCs (FE<sub>C<sub>2</sub>H<sub>4</sub></sub> = 32.5%). As shown in Figure 4c, Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C achieves a FE<sub>C<sub>2</sub>H<sub>4</sub></sub> of 60.4% at a high current density of 300 mA cm<sup>–2</sup>, corresponding to a partial current density towards C<sub>2</sub>H<sub>4</sub> (*j*<sub>C<sub>2</sub>H<sub>4</sub></sub>) as high as 181.2 mA cm<sup>–2</sup>. The corresponding FE<sub>C<sub>2</sub>H<sub>4</sub></sub>/FE<sub>CH<sub>4</sub></sub> ratio reaches a maximum of 17.3, indicating that the reaction pathway of CO<sub>2</sub>-to-C<sub>2</sub>H<sub>4</sub> conversion is more favorable, and CH<sub>4</sub> generation is significantly suppressed in the basic solution.<sup>[32]</sup> The remarkable FE<sub>C<sub>2</sub>H<sub>4</sub></sub> and *j*<sub>C<sub>2</sub>H<sub>4</sub></sub> make Cu NCs/Al<sub>2</sub>O<sub>3</sub>-10C superior to the reported colloidal Cu NCs-based electrocatalysts in the gas-feed flow

electrolyzer with strong alkaline electrolyte, such as Cu nanocubes<sup>[7]</sup> ( $\text{FE}_{\text{C}_2\text{H}_4} = 60\%$ ,  $j_{\text{C}_2\text{H}_4} = 144 \text{ mA cm}^{-2}$ ) and Cu cubes<sup>[33]</sup> ( $\text{FE}_{\text{C}_2\text{H}_4} = 57\%$ ,  $j_{\text{C}_2\text{H}_4} = 171 \text{ mA cm}^{-2}$ ). Stability tests for  $\text{CO}_2$  electrolysis were carried out at a constant potential of  $-1.1 \text{ V}$  vs. RHE in  $5 \text{ M KOH}$ . The  $j_{\text{total}}$  and  $\text{FE}_{\text{C}_2\text{H}_4}$  displayed a smaller drop of  $9.7\%$  and  $3.3\%$  within  $24 \text{ h}$  electrolysis on Cu NCs/ $\text{Al}_2\text{O}_3$ -10C at  $-1.1 \text{ V}$  vs. RHE, compared to  $39.0\%$  and  $40.0\%$  decay for Cu NCs, respectively (Figure 4d). A continuous size evolution from monodisperse nanoparticles to large aggregated clusters was observed on Cu NCs over time, whereas ALD overcoating effectively minimized the motion of Cu NCs driven by the electric field or adsorption/desorption of intermediates under the harsh conditions of high current density and pH (Figure S22).<sup>[34]</sup>

## Conclusion

In summary, we used ALD to deposit ultrathin  $\text{Al}_2\text{O}_3$  onto supported Cu NCs to selectively cover (111) facets by switching the precursor pulse sequences. The overcoated Cu NCs with a high ratio of (100)/(111) not only display remarkable improvement of  $\text{C}_2\text{H}_4$  faradaic efficiency and suppression of  $\text{CH}_4$  generation, but also prevent the dynamic motion and aggregation of the NCs under harsh conditions. In a gas-feed flow electrolyzer in  $5 \text{ M KOH}$ , Cu NCs/ $\text{Al}_2\text{O}_3$ -10C achieves a high  $\text{FE}_{\text{C}_2\text{H}_4}$  of  $60.4\%$  with a current density of  $-300 \text{ mA cm}^{-2}$  and negligible activity/selectivity degradation over  $24 \text{ h}$ . This facet-selective deposition strategy shows promise as a general approach for tuning the selectivity and enhancing the stability of  $\text{CO}_2$ RR on Cu NCs-based catalysts.

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## Conflict of Interest

The authors declare no conflict of interest.

**Keywords:** atomic layer deposition ·  $\text{CO}_2$  reduction · copper nanocrystals · facet-selective · stability

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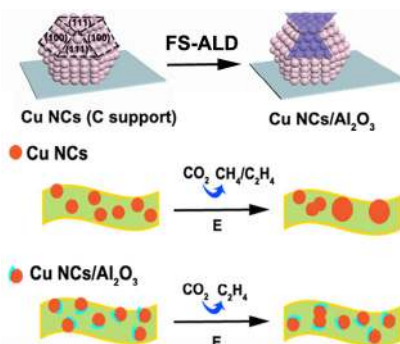
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## Communications

CO<sub>2</sub> Reduction

H. Li, P. Yu, R. Lei, F. Yang, P. Wen, X. Ma,  
G. Zeng, J. Guo, F. M. Toma, Y. Qiu,  
S. M. Geyer, X. Wang, T. Cheng,\*  
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Facet-Selective Deposition of Ultrathin  
Al<sub>2</sub>O<sub>3</sub> on Copper Nanocrystals for Highly  
Stable CO<sub>2</sub> Electroreduction to Ethylene

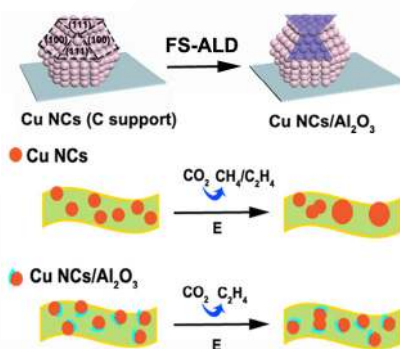


A facet-selective atomic layer deposition (FS-ALD) technique was employed to selectively cover the (111) facets of Cu NCs with ultrathin Al<sub>2</sub>O<sub>3</sub>, which significantly increases the faradaic efficiency ratio of C<sub>2</sub>H<sub>4</sub>/CH<sub>4</sub> in both H-type and GDE flow cells. This Al<sub>2</sub>O<sub>3</sub> overcoating also effectively suppresses the dynamic mobility and aggregation of Cu NCs during CO<sub>2</sub>RR.

CO<sub>2</sub> Reduction

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A facet-selective atomic layer deposition (FS-ALD) technique was employed to selectively cover the (111) facets of Cu NCs with ultrathin Al<sub>2</sub>O<sub>3</sub>, which significantly increases the faradaic efficiency ratio of C<sub>2</sub>H<sub>4</sub>/CH<sub>4</sub> in both H-type and GDE flow cells. This Al<sub>2</sub>O<sub>3</sub> overcoating also effectively suppresses the dynamic mobility and aggregation of Cu NCs during CO<sub>2</sub>RR.



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